OIPE	400
APR 02 20	
BATTAN CE FRADE	ASS .

1

= S

PATENT Attorney Docket No. 04329.3304-00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ayako NAKANO et al.

Application No.: 10/823,539

Filed: April 14, 2004

For: PATTERN FORMING METHOD AND SYSTEM, AND METHOD OF MANUFACTURING A SEMICONDUCTOR DEVICE Group Art Unit: 1756

Examiner: Stephen D. ROSASCO

Confirmation No.: 4440

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

RESPONSE TO RESTRICTION REQUIREMENT

In a Restriction Requirement mailed March 1, 2007, the period for response to

which extends through April 2, 2007 (April 1 is a Sunday), the Examiner required

restriction under 35 U.S.C. § 121 between:

Group I: Claims 1-12 and 25¹, characterized by the Examiner as

drawn to a mask pattern forming method and classified in class 430,

subclass 5; and

Group II: Claims 13-24, characterized by the Examiner as drawn to

a system for making a photomask and classified in class 716, subclass 21.

¹ The Restriction Requirement as mailed does not indicate whether pending claim 25 should be included in Group I or Group II, if either. In a telephone interview on March 30, 2007, Examiner Rosasco explained that claim 25 should have been included in Group I.

Applicants elect to prosecute Group I, claims 1-12 and 25, without traverse.

Please grant any extensions of time required to enter this response and charge

any additional required fees to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L.P.

By:

Dated: April 2, 2007

Reece Nienstadt Reg. No. 52,072

RVB/RWN

4

Ŧ